

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	559	438/478.ccls.	US-PGPUB; USPAT	OR	OFF	2006/07/17 13:43
L5	347	(substrate wafer silicon) same ((ge germane germanium germano\$10) with (cvd pecvd (chemical adj vapor) epitax\$8) with (precursor ((source process raw) adj gas)))	US-PGPUB; USPAT	OR	ON	2006/07/17 14:03
L6	58	L5 same (two second)	US-PGPUB; USPAT	OR	ON	2006/07/17 14:03
L7	1797	438/478.ccls. 438/503.ccls. 438/507.ccls. 427/255.28.ccls. 257/65.ccls.	US-PGPUB; USPAT	OR	OFF	2006/07/17 14:12
L8	70	L7 and ((ge germane germanium germano\$10) same (cvd pecvd (chemical adj vapor) epitax\$8) same (precursor ((source process raw) adj gas)))	US-PGPUB; USPAT	OR	ON	2006/07/17 14:12
L9	17	("4605479"   "4649059"   "4723508"   "4786352"   "4800173"   "4843030"   "4942058").PN. OR ("5120394").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/07/17 14:25
L10	64	(substrate wafer silicon) and ((ge germane germanium germano\$10) same (cvd pecvd (chemical adj vapor) epitax\$8) same (precursor ((source process raw) adj gas)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/17 14:27
L11	546	((substrate wafer silicon) and (ge germane germanium germano\$10) and (chamber cvd pecvd (chemical adj vapor) epitax\$8) and (compound precursor ((source process raw) adj gas))).clm.	US-PGPUB	OR	ON	2006/07/17 14:36
L12	257	((substrate wafer silicon) and (chamber cvd pecvd (chemical adj vapor) epitax\$8) and ((ge germane germanium germano\$10) with (compound precursor ((source process raw) adj gas)))).clm.	US-PGPUB	OR	ON	2006/07/17 14:40